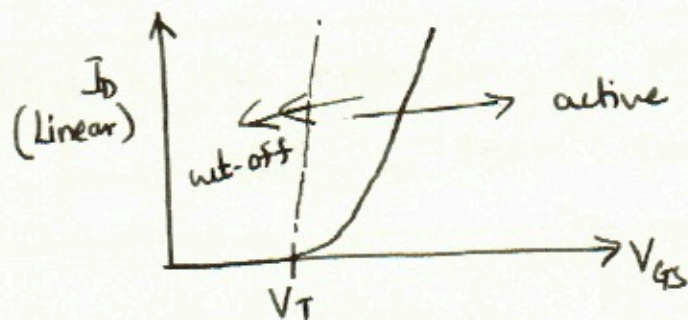


Subthreshold Conduction \Rightarrow also called subthreshold leakage.

If we look at the $I_D - V_{GS}$ plot on a linear scale, it appears as

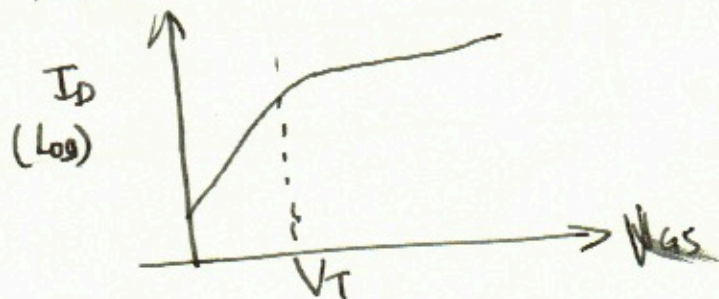


cut-off = OFF
active = ON

The region $V_{GS} < V_T$ is called the cut-off region, while $V_{GS} > V_T$ is called the active region.

However, the current does not abruptly drop to zero for $V_{GS} \leq V_T$. MOSFET still conducts some current for $V_{GS} < V_T$. This regime of operation is called SUB-THRESHOLD CONDUCTION. (or leakage in sub-threshold / off state leakage)

If we look at $I_D - V_{GS}$ plot on a log-scale, we can see this more clearly.



On the log scale, it is clear that current varies exponentially with V_{GS} in the sub-threshold region.

That is, the transition of MOSFET operation from "on" to "off" conditions is NOT ABRUPT.

The actual relationship of $I_D - V_{GS}$ for sub-threshold is given as :-

$$I_D = I_0 \exp\left(\frac{q(V_{GS} - V_T)}{n k_B T}\right) \left(1 - \exp\left(-\frac{q V_{DS}}{k_B T}\right)\right)$$

$$\frac{k_B T}{q} = \text{Thermal voltage} = 25.8 \text{ mV at } 300\text{K}$$

When $V_{DS} \gg \frac{k_B T}{q}$ then second term in the current expression goes away. And we get :-

$$I_D = I_0 \exp\left(\frac{q(V_{GS} - V_T)}{n k_B T}\right)$$

SUB-THRESHOLD
CURRENT
FOR $V_{DS} \gg \frac{k_B T}{q}$

What is n?

'n' is called the non-ideality factor.

The best-case or ideal value for n is unity.

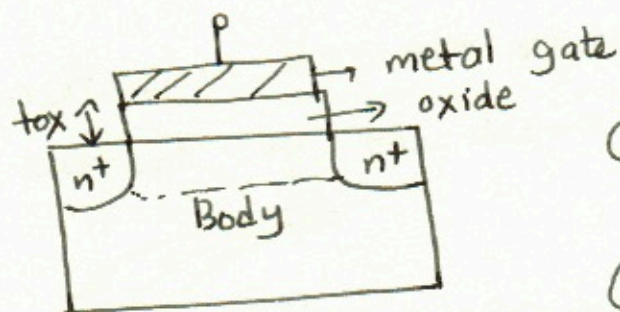
However, in real transistors, 'n' usually varies between 1.0 and 1.5.

The physical definition of n is given as

$$n = \left(1 + \frac{C_{dep}}{C_{ox}} \right)$$

C_{dep} = Depletion capacitance

C_{ox} = oxide capacitance.

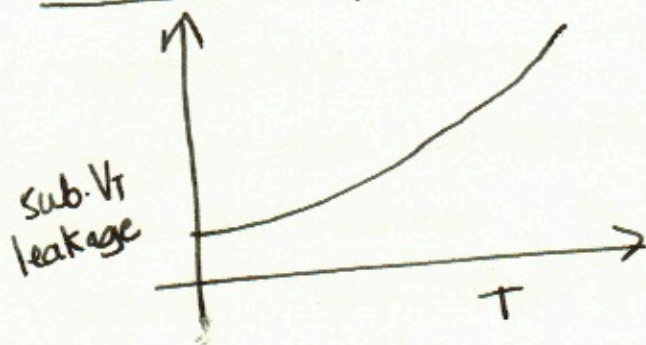


$$C_{ox} = \frac{\epsilon_{ox}}{tox}$$

C_{dep} = Depletion capacitance
in the body
at inversion

Depends on
doping and
surface potential
at inversion.

Effect of temperature on sub-threshold leakage

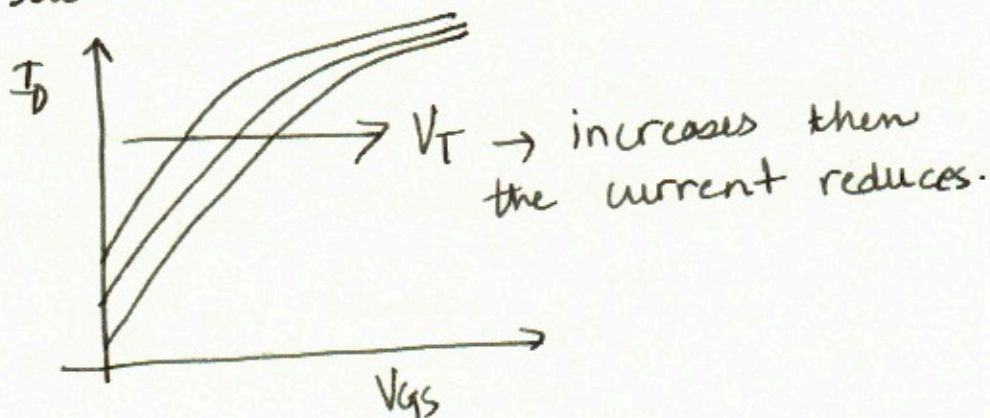


Effect of V_T on sub-threshold leakage

$$I_D = I_0 \exp\left(\frac{q(V_{GS} - V_T)}{n K_B T}\right)$$

As $V_T \uparrow \rightarrow I_D \downarrow \rightarrow$ good for sub-threshold leakage.

However, increase in V_T also reduces the ON state current of the device.



In digital applications, the presence of subthreshold current is undesirable.

For an ideal switch-like behavior, we want the current to drop as fast as possible once the gate-source voltage falls below V_T .

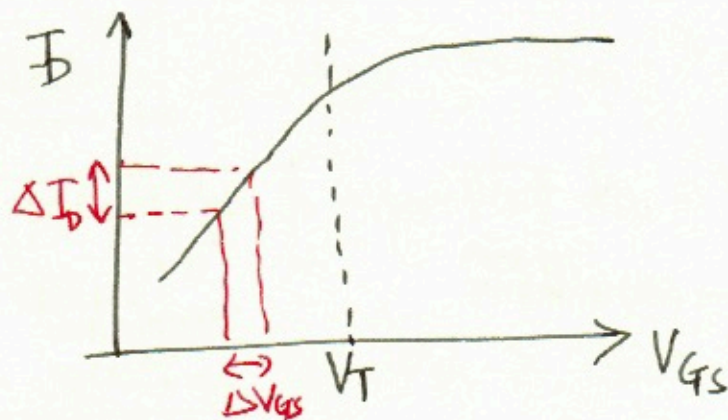
The "goodness" of the mosfet switch is quantified by the parameter sub-threshold slope, S .

$$S = n \left(\frac{k_B T}{q} \right) \underbrace{\log_e(10)}_{2.3}$$

$$\boxed{S = 2.3 n \left(\frac{k_B T}{q} \right)} \rightarrow \left\{ \begin{array}{l} \text{unit: -} \\ \text{mV/decade} \end{array} \right\}$$

We want 'S' to be as small as possible. The smallest value of S possible is 60 mV/decade.

'S' tells us how much of gate-source voltage drop is needed to reduce I_D by one decade in sub-threshold.



'S' tells us how much ΔV_{GS} we need so that ΔI_D changes by one order of magnitude.

Since $n=1$, best case value of $S = 2.3 \left(\frac{k_B T}{q} \right)$
 \Downarrow
 26 mV
 $= \underline{\underline{60 \text{ mV/decade}}}$